

[STNS USPAT2 - Update 10/02]
STN Columbus

(FILE 'HOME' ENTERED AT 15:40:20 ON 19 OCT 2002)

FILE 'USPAT2' ENTERED AT 15:40:47 ON 19 OCT 2002

L1 2618 S RESIST# OR PHOTORESIST#
L2 101 S HARD(BA)MASK#
L3 16726 S ETCH? OR PATTERN? OR REMOVE? OR PATTERN?
L4 3393 S PLASMA? OR SPUTTER? OR CORONAT? OR RIE OR MRIE OR MERIE OR GLO
L5 24 S L1(P) L2(P) L3(P) L4
L6 6114 S INSERT(BA)GAS? OR N2 OR HE OR AR OR KR OR XE OR N(3W)2
L7 4047 S ARGON OR HELIUM OR XENON OR NITROGEN OR NEON
L8 5 S L5, L6 OR L7
L9 4059 S C(BW)2 OR O(BW)2 OR OXYGEN? OR O2 OR O3
L10 5 S L8, P, L9 OR OZONE
L11 3 S L8 OR CO OR COXIDE OR SO OR SO2 OR CLC OR CLO2 OR NO
L12 5 S L10 OR L11
L13 1 S L12(P) OR F2F# OR NF# OR SF# OR CHF# OR CH2F2 OR CH3F
L14 2 S L12 OR L13
L15 1531 S BILAYER OR BILAYER OF MULTILAYER OR MULTI(W)LEVEL? OR MULTI(W)
L16 2 S L11(P) L15(P) L9, P, L4, P, L6 OR L7
L17 3 S L16 NOT L8
L18 444 S (RESIST# OR PHOTORESIST#)/CLM
L19 188 S (HARD(BA)MASK? OR BILAYER OR BILAYER OF MULTILAYER OF MULTILE
L20 0 S MULTIL/CLM
L21 692 S MULTIL/CLM
L22 4940 S (ETCH? OR PATTERN? OR REMOVE? OR PATTERN?)/CLM
L23 656 S (PLASMA? OR SPUTTER? OR CORONAT? OR RIE OR MRIE OR MERIE OR GLO
L24 46 S (PATTERN(BA)ION), CLM
L25 0 S L16 AND (L19 OR L21) AND L22 AND (L23 OR L24)
L26 1051 S (INSERT(BA)GAS? OR N2 OR HE OR AR OR KR OR XE OR N(3W)2)/CLM
L27 833 S (ARGON OR HELIUM OR XENON OR NITROGEN OR NEON)/CLM
L28 3 S L25 AND (L26 OR L27)
L29 3 S L28 NOT L17
L30 1 S L28 NOT L8

STN & Cas, Japic, Inspec - Update 10/12/01

(FILE 'HOME' ENTERED AT 18:37:01 ON 18 OCT 2002)

FILE 'CA' ENTERED AT 18:37:11 ON 18 OCT 2002

L1 59003 S RESIST OR PHOTORESIST
L2 902 S HARD(3A)MASK?
L3 1578103 S ETCH? OR PATERN? OR PATTERN? OR REMOV?
L4 804528 S PLASMA# OR SPUTTER? OR CORONA OR RIE OR MRIE OR
GLOW
L5 16640 S LOW(3W)(K OR DIELECTRIC?)
L6 1035740 S N2 OR NITROGEN? OR INERT(3A)GAS? OR AR OR KR OR XE OR HE
OR A
L7 297991 S N(3W)2
L8 164 S L1 AND L2 AND L3 AND L4
L9 58 S L8 AND (L6 OR L7)
L10 6 S L5 AND L9
L11 32 S L9 AND POLY?
L12 33 S L10 OR L11
L13 5 S L9 AND (POLYI? OR POLYA?)
L14 16 S L9 AND POLYM?
L15 21 S L10 OR L13 OR L14

FILE 'JAPIO' ENTERED AT 18:42:00 ON 18 OCT 2002

L16 0 S L15

FILE 'INSPEC' ENTERED AT 18:42:26 ON 18 OCT 2002

L17 3 S L15

WEST Search History

10/18/02

DATE: Friday, October 18, 2002

Set Name Query

side by side

DB TDBD; PLUR YES; OP OR

L20 L19 and 118 and 117 and 116 0 L20

L19 n2 or nitrogen or ar or argon or he or helium or ne or neon or kr or krypton or inert near3 gas\$ or xe or xenon 3893 L19

L18 etch\$ or patern\$ or pattern\$ or remov\$ 22249 L18

L17 hard near3 mask? 1 L17

L16 resist or photoresist 3526 L16

DB-DWPI; PLUR YES; OP OR

L15 113 and (114 or poly\$) 0 L15

L14 low near3 (k or dielectric\$) 7611 L14

L13 L12 and 111 and 110 and 19 6 L13

L12 n2 or nitrogen or ar or argon or he or helium or ne or neon or kr or krypton or inert near3 gas\$ or xe or xenon 1255698 L12

L11 etch\$ or patern\$ or pattern\$ or remov\$ 1243038 L11

L10 hard near3 mask? 58 L10

L9 resist or photoresist 84478 L9

DB USPT,PGPB; PLUR YES; OP OR

L8 15 same (16 or poly\$) 0 L8

L7 L5 and (16 or polymer\$) 5 L7

L6 low near3 (k or dielectric\$) 24819 L6

L5 L4 same 13 same 12 same 11 9 L5

L4 n2 or nitrogen or ar or argon or he or helium or ne or neon or kr or krypton or inert near3 gas\$ or xe or xenon 767000 L4

L3 etch\$ or patern\$ or pattern\$ or remov\$ 1982651 L3

L2 hard near3 mask? 384 L2

L1 resist or photoresist 213659 L1

END OF SEARCH HISTORY